EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	3	(("5705299") or ("6078381") or ("6545274")).PN.	US-PGPUB; USPAT	OR	OFF	2006/03/11 20:11
L2	51858	(mask or reticle) near3 first	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/11 20:11
L3	45325	(mask or reticle) near3 second	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/11 20:11
L4	30432	2 and 3	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/11 20:24
L5	923	(mask or reticle) near5 (gate near line)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/11 20:25
L6	9146	(mask or reticle) near5 (pixel)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/11 20:26
L7	8	(mask or reticle) near5 (driver near pattern)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/11 20:25
L8	1	5 and 6 and 7	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/11 20:25

L9	305	(mask or reticle) near5 (pixel near pattern)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/11 20:26
L10	18	9 and 5	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/11 20:27
L11	892	5 and (substrate or wafer)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/11 20:27
L12	12	11 and (pitch near6 (mask or reticle))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/11 20:28
L13	12	11 and 12	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/11 20:29
L14	880	11 not 12	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/11 20:29
L15	865	14 not 10	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/11 20:29
L16	740	15 and (expos$5 or project$3)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/11 20:30

EAST Search History

L17	6	16 and ("355"/$.ccls.)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/11 20:33
L18	734	16 not 17	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/11 20:33

EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L24	7	(((mask or reticle or expos$5) and (pattern or design) near6 pitch) and ((driv$3 or moving or moved or moves or move or movement) and (substrate or wafer) near6 pitch)).clm.	US-PGPUB	OR	ON	2006/03/11 20:44